

F(α)

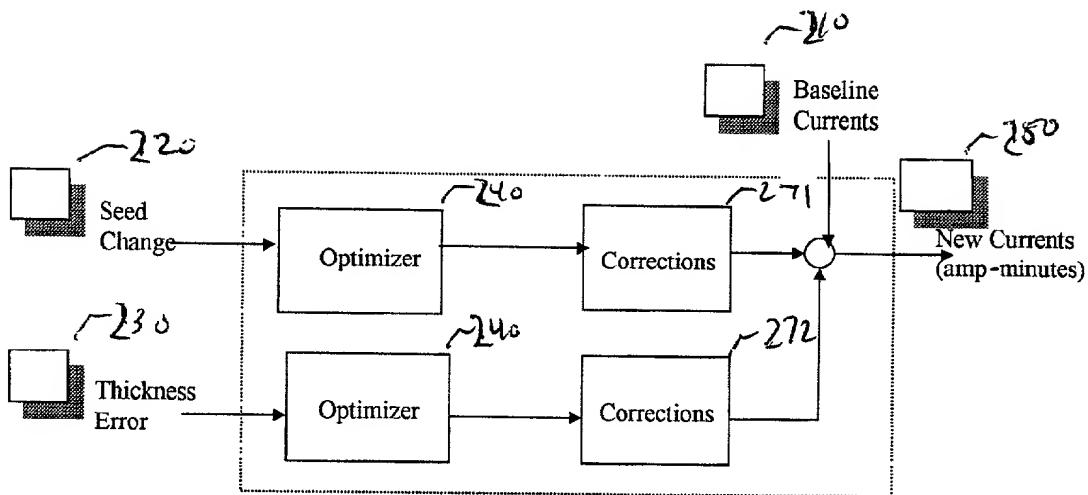
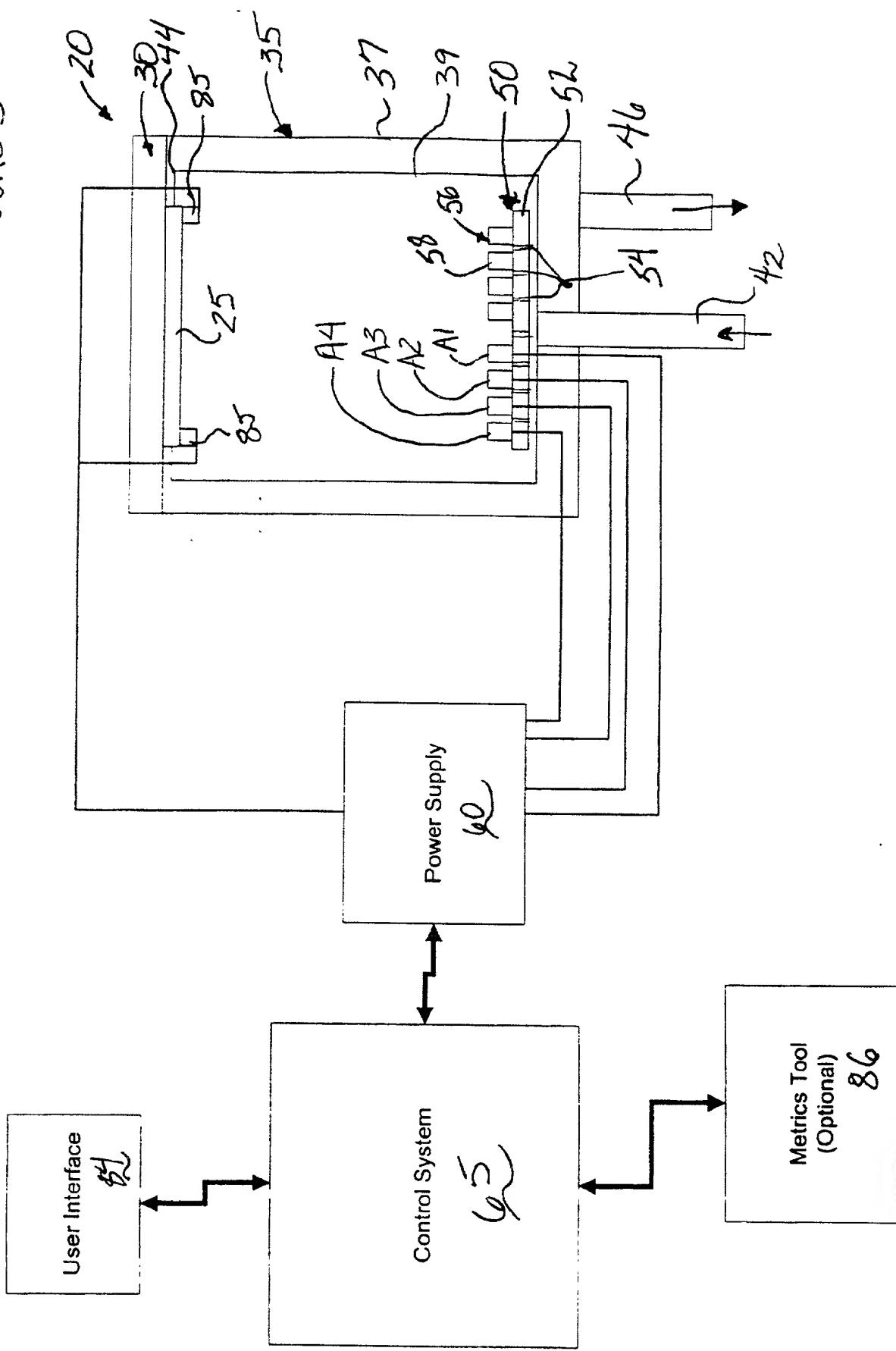
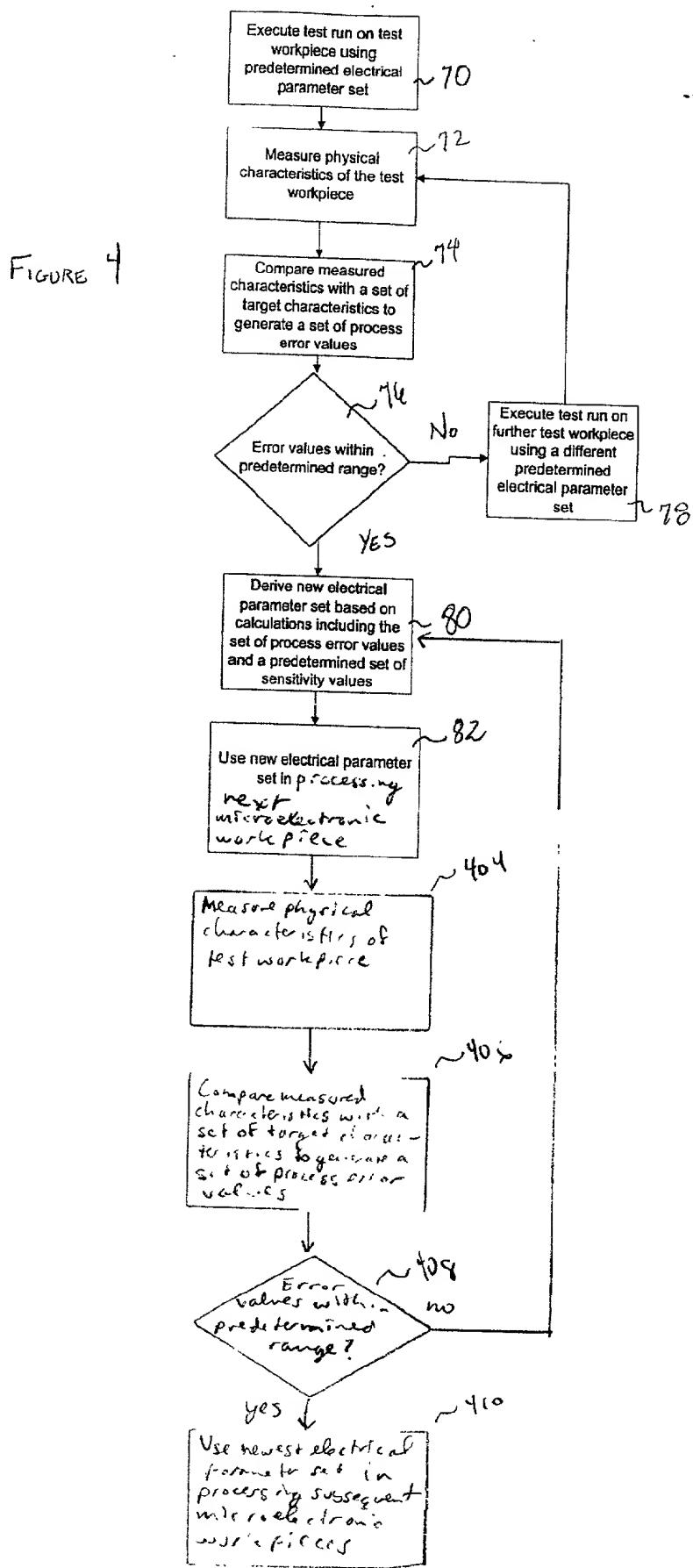


Fig 2

FIGURE 5





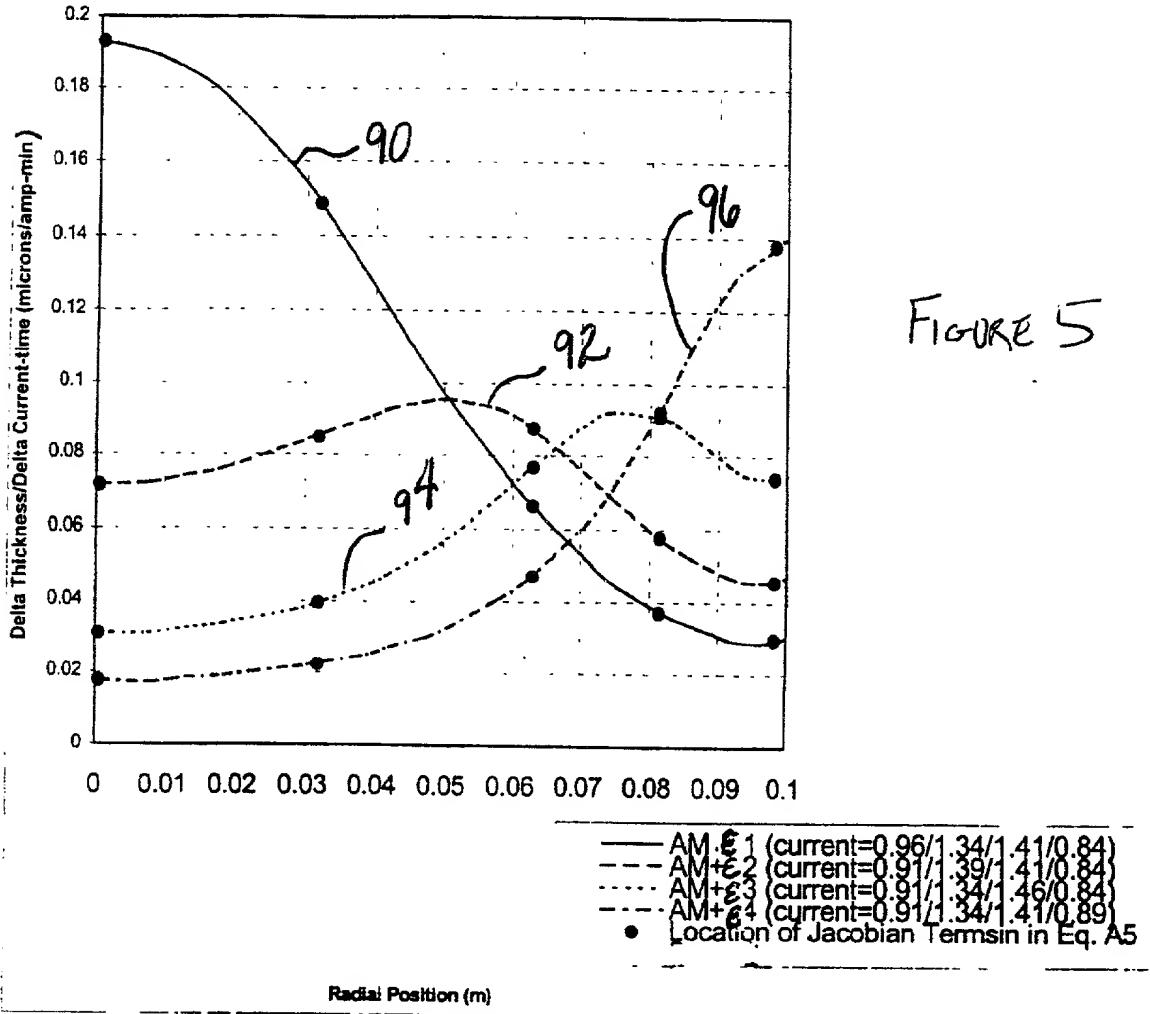
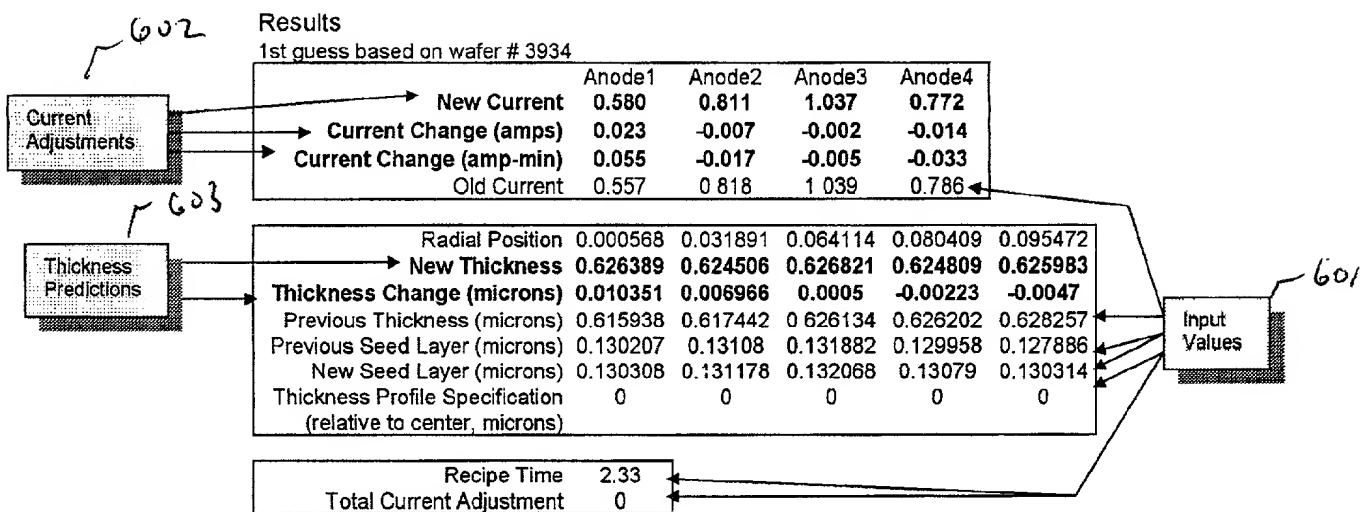


FIGURE 5



F 16 6

702 Results

2nd guess based on wafer #4004

current
adjustments

	Anode1	Anode2	Anode3	Anode4
New Current	0.578	0.831	1.008	0.783
Current Change (amps)	-0.002	0.020	-0.029	0.011
Current Change (amp-min)	-0.005	0.046	-0.068	0.027
Old Current	0.580	0.811	1.037	0.772

703

thickness
prediction

input
values

Radial Position	0.000568	0.031891	0.064114	0.080409	0.095472
New Thickness	0.623077	0.621834	0.623362	0.622034	0.622809
Thickness Change (microns)	0.001166	0.001714	-0.00068	-0.00199	0.00082
Previous Thickness (microns)	0.624351	0.621553	0.622704	0.62076	0.618746
Previous Seed Layer (microns)	0.130308	0.131178	0.132068	0.13079	0.130314
New Seed Layer (microns)	0.127869	0.129744	0.133403	0.134055	0.133556
Thickness Profile Specification (relative to center, microns)	0	0	0	0	0

Recipe Time	2.33
Total Current Adjustment	0

F(G)